L Number				
	119259	Search Text 438/\$.ccls. or 257/\$.ccls.	DB USPAT;	Time stamp 2003/02/13 15:43
			US-PGPUB	
_ !	12479	(implanting implanted implant) with	USPAT;	2003/02/14 10:59
		(nitrogen trifluoronitride ammonia	US-PGPUB	
		(nitrous adj oxide) (nitric adj oxide)		
		"n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2		
		o" "no")		
-	13765	(implanting implanted implant) with	USPAT;	2003/02/13 15:47
		(silicon (silicon adj tetrafluoride)	US-PGPUB	1
		silane dichlorosilane trichlorosilande		
		(silicon adj tetrachloride) "siF.sub.4"		
		"siH.sub4" "siH.sub.2 cl.sub.2"		
	4704	"siCl.sub.3" "sicl.sub.4")		0000 (00 (14 10 50
-	4794	(438/\$.ccls. or 257/\$.ccls.) and	USPAT;	2003/02/14 10:53
		((implanting implanted implant) with	US-PGPUB	
		(nitrogen trifluoronitride ammonia		
	71	(nitrous adj oxide) (nitric adj oxide)		
	R	"n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))		
	11952	(438/\$.ccls. or 257/\$.ccls.) and	USPAT;	2003/02/13 15:47
_	11952	((implanting implanted implant) with	US-PGPUB	2003/02/13 13:47
		(silicon (silicon adj tetrafluoride)	U3-FGFUB	
		silane dichlorosilane trichlorosilande		
		(silicon adj tetrachloride) "siF.sub.4"		
		"siH.sub4" "siH.sub.2 cl.sub.2"		
		"siCl.sub.3" "sicl.sub.4"))		
_	44	((438/\$.ccls. or 257/\$.ccls.) and	USPAT;	2003/02/13 15:54
		((implanting implanted implant) with	US-PGPUB	2003/02/13 13:31
		(silicon (silicon adj tetrafluoride)	100 10100	3
		silane dichlorosilane trichlorosilande	1	
		(silicon adj tetrachloride) "siF.sub.4"		
		"siH.sub4" "siH.sub.2 cl.sub.2"		
		"siCl.sub.3" "sicl.sub.4"))) and (uniform	1	
		near3 thickness\$ near3 dielectric)		
_	12	((438/\$.ccls. or 257/\$.ccls.) and	USPAT;	2003/02/13 16:04
		((implanting implanted implant) with	US-PGPUB	
		(nitrogen trifluoronitride ammonia		
		(nitrous adj oxide) (nitric adj oxide)		
		"n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2		
		o" "no"))) and (uniform near3 thickness\$		
		near3 dielectric)		
-	35	(((438/\$.ccls. or 257/\$.ccls.) and	USPAT;	2003/02/13 16:34
		((implanting implanted implant) with	US-PGPUB	į
		(silicon (silicon adj tetrafluoride)		i
	1	silane dichlorosilane trichlorosilande		
		(silicon adj tetrachloride) "siF.sub.4"		
		"siH.sub4" "siH.sub.2 cl.sub.2"		
		"siCl.sub.3" "sicl.sub.4"))) and (uniform	1	
		near3 thickness\$ near3 dielectric)) not		
		(((438/\$.ccls. or 257/\$.ccls.) and		
		((implanting implanted implant) with		
		(nitrogen trifluoronitride ammonia		
		(nitrous adj oxide) (nitric adj oxide)	1	1
		"n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2		
	NI a	o" "no"))) and (uniform near3 thickness\$		
		near3 dielectric))	USPAT;	2003/02/13 16:35
-	1	("6465373").PN.	US-PGPUB	2003/02/13 10:33
	0	(("6465373").PN.) and (implanting	USPAT;	1 2003/02/13 16:59
	0	(("6465373").PN.) and (Implanting   implanted implant)	US-PGPUB	1 2003/02/13 10.39
	36		USPAT;	2003/02/13 17:46
	36	((implanting implanted implant) with	US-PGPUB	2003/02/13 17.40
		((intriding nitridization))	05 1GEOD	
	4	RTN with (implanting implanted implant	USPAT;	2003/02/13 17:47
	4	implantation)	US-PGPUB	2003,02/13 17.47
_	255833	capacitor DRAM	USPAT;	2003/02/14 10:54
	200000	ontropicor pigni	US-PGPUB	1 2000, 02, 11 10.04

	122	<pre>(capacitor DRAM) and (((implanting implant implanted) with (angle)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2"</pre>	USPAT; US-PGPUB	2003/02/14 11:03
-	132	"nf.sub.3" "nh.sub.3" "n.sub.2 o" "no")) (capacitor DRAM) and (((implanting implant implanted) with (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))	USPAT; US-PGPUB	2003/02/14 15:45
-		((capacitor DRAM) and (((implanting implant implanted) with (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))) not ((capacitor DRAM) and (((implanting implant implanted) with (angle)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj	USPAT; US-PGPUB	2003/02/14 15:07
-	34	oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))) (capacitor DRAM) and (((doping doped dope) with (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2"	USPAT; US-PGPUB	2003/02/14 14:04
-	242	"nf.sub.3" "nh.sub.3" "n.sub.2 o" "no")) (capacitor DRAM) and (((implanting implant implanted) with (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3" "sicl.sub.4"))	USPAT; US-PGPUB	2003/02/14 15:23
-	15	((capacitor DRAM) and (((doping doped dope) with (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))) not ((capacitor DRAM) and (((implanting implant implanted) with (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2	USPAT; US-PGPUB	2003/02/14 14:06
	170	o" "no"))) ((capacitor DRAM) and (((implanting implant implanted) with (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3" "sicl.sub.4"))) not ((capacitor DRAM) and (((implanting implant implanted) with (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2	USPAT; US-PGPUB	2003/02/14 14:46
-	180	o" "no"))) (capacitor DRAM) and (((implanting implant implanted) same (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide)(nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))	USPAT; US-PGPUB	2003/02/14 15:22
-	27	(uniform uniformity) with ((silicon adj nitride) "si.sub.3 N.sub.4") with (implanting implanted doped doping doped implant)	USPAT; US-PGPUB	2003/02/14 14:49

	<del></del>			
-	58	( (	USPAT;	2003/02/14 15:04
		implant implanted) same (angle angled))	US-PGPUB	
		same (nitrogen trifluoronitride ammonia		İ
		(nitrous adj oxide) (nitric adj oxide)		
ĺ		"n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2		
	,	o" "no"))) not ((capacitor DRAM) and		
		(((implanting implant implanted) with		
		(angle)) same (nitrogen trifluoronitride		
		ammonia (nitrous adj oxide)(nitric adj		1
		oxide) "n.sub.2" "nf.sub.3" "nh.sub.3"		
		"n.sub.2 o" "no")))		
-	135	(capacitor DRAM) and (((doping doped dope)	USPAT;	2003/02/14 15:17
		same (angle angled)) same (nitrogen	US-PGPUB	
		trifluoronitride ammonia (nitrous adj		
		oxide)(nitric adj oxide) "n.sub.2"		ļ
		"nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))		
-	304	(capacitor DRAM) and (((implanting implant	USPAT;	2003/02/14 15:20
		implanted) same (angle angled)) same	US-PGPUB	
		(silicon (silicon adj tetrafluoride)		
		silane dichlorosilane trichlorosilande		
		(silicon adj tetrachloride) "siF.sub.4"		
	1	"siH.sub4" "siH.sub.2 cl.sub.2"		
		"siCl.sub.3" "sicl.sub.4"))		
_	41		USPAT;	2003/02/14 15:14
		implant implanted) same (angle angled))	US-PGPUB	
		same (silicon (silicon adj tetrafluoride)		1
		silane dichlorosilane trichlorosilande		
		(silicon adj tetrachloride) "siF.sub.4"		
		"siH.sub4" "siH.sub.2 cl.sub.2"		
		"siCl.sub.3" "sicl.sub.4"))) not		
		(((capacitor DRAM) and (((implanting		
		<pre>implant implanted) with (angle angled))</pre>		
		same (silicon (silicon adj tetrafluoride)		1
		silane dichlorosilane trichlorosilande		
		(silicon adj tetrachloride) "siF.sub.4"		1
		"siH.sub4" "siH.sub.2 cl.sub.2"		
		"siCl.sub.3" "sicl.sub.4"))) ((capacitor		
		DRAM) and (((implanting implant implanted)		
		with (angle)) same (nitrogen		1
		trifluoronitride ammonia (nitrous adj		İ
		oxide) (nitric adj oxide) "n.sub.2"	-	
		"nf.sub.3" "nh.sub.3" "n.sub.2 o" "no")))		
		(((capacitor DRAM) and (((implanting		
		implant implanted) same (angle angled))		
		same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide)		1 -
		"n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2		
		o" "no"))) not ((capacitor DRAM) and		
		(((implanting implant implanted) with		
		(angle)) same (nitrogen trifluoronitride		
		ammonia (nitrous adj oxide) (nitric adj		
		oxide) "n.sub.2" "nf.sub.3" "nh.sub.3"	1	1
		"n.sub.2 o" "no")))))		
-	1	("6326277").PN.	USPAT;	2003/02/14 15:14
			US-PGPUB	1 1
-	1	(("6326277").PN.) and (silicon adj	USPAT;	2003/02/14 15:15
		nitride)	US-PGPUB	
-	311	(capacitor DRAM) and (((doped doping dope)	USPAT;	2003/02/14 15:19
		same (angle angled)) same (silicon	US-PGPUB	
		(silicon adj tetrafluoride) silane		
		dichlorosilane trichlorosilande (silicon		
		adj tetrachloride) "siF.sub.4" "siH.sub4"		
		"siH.sub.2 cl.sub.2" "siCl.sub.3"	1	
	<u> </u>	"sicl.sub.4"))		<u> </u>

			····	
	203	((capacitor DRAM) and (((doped doping dope) same (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3" "sicl.sub.4"))) not ((capacitor DRAM) and (((implanting implant implanted) same (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3"	USPAT; US-PGPUB	2003/02/14 15:20
	74	"sicl.sub.4"))) ((capacitor DRAM) and (((doping doped dope) same (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj oxide) (nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))) not ((capacitor DRAM) and (((implanting implant implanted) same (angle angled)) same (nitrous adj oxide) (nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no")))	USPAT; US-PGPUB	2003/02/14 15:21
	203	<pre>(((capacitor DRAM) and (((doped doping dope) same (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3" "sicl.sub.4"))) not ((capacitor DRAM) and (((implanting implant implanted) same (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3" "sicl.sub.4"))) not ((capacitor DRAM) and (((implanting implant implanted) with (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub2 cl.sub.2" "siCl.sub.3"</pre>	USPAT; US-PGPUB	2003/02/14 15:23
	198	"sicl.sub.4"))) (((capacitor DRAM) and (((doped doping dope) same (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3" "sicl.sub.4"))) not ((capacitor DRAM) and (((implanting implant implanted) same (angle angled)) same (silicon (silicon adj tetrafluoride) silane dichlorosilane trichlorosilande (silicon adj tetrachloride) "siF.sub.4" "siH.sub4" "siH.sub.2 cl.sub.2" "siCl.sub.3" "sicl.sub.4"))) not ((capacitor DRAM) and (((implanting implant implanted) same (angle angled)) same (nitrogen trifluoronitride ammonia (nitrous adj	USPAT; US-PGPUB	2003/02/14 15:24
-	1	oxide)(nitric adj oxide) "n.sub.2" "nf.sub.3" "nh.sub.3" "n.sub.2 o" "no"))) 09/385787	USPAT;	2003/02/14 15:32
-	1	("6159785").PN.	US-PGPUB USPAT;	2003/02/14 15:32
-	1	(("6159785").PN.) and (silicon adj nitride)	US-PGPUB USPAT; US-PGPUB	2003/02/14 15:32
		<u> </u>	·	•

_	3	(capacitor DRAM) and (((implanting implant	USPAT;	2003/02/14 15:47
-		implanted dope doping doped) with (angle	US-PGPUB	
		angled)) same (nitrogen "si.sub.3		
		n.sub.4") same (uniformity uniform))		